



# Auger effect limited performance in tunnel field effect transistors

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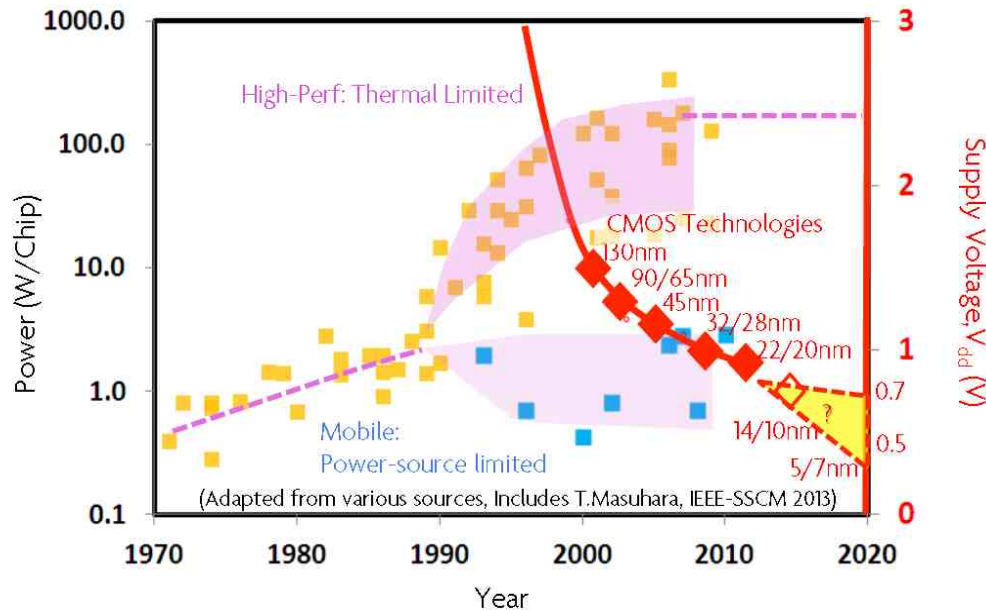
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# The Challenge of semiconductor industry

## Power Crisis



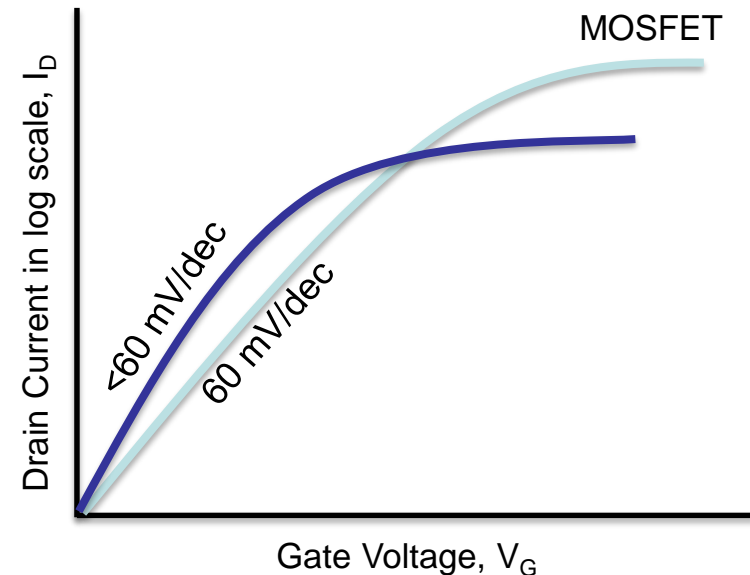
Scaling of  $V_{DD}$

Low power transistors → low subthreshold swing

## Lower Subthreshold Swing

Applications:

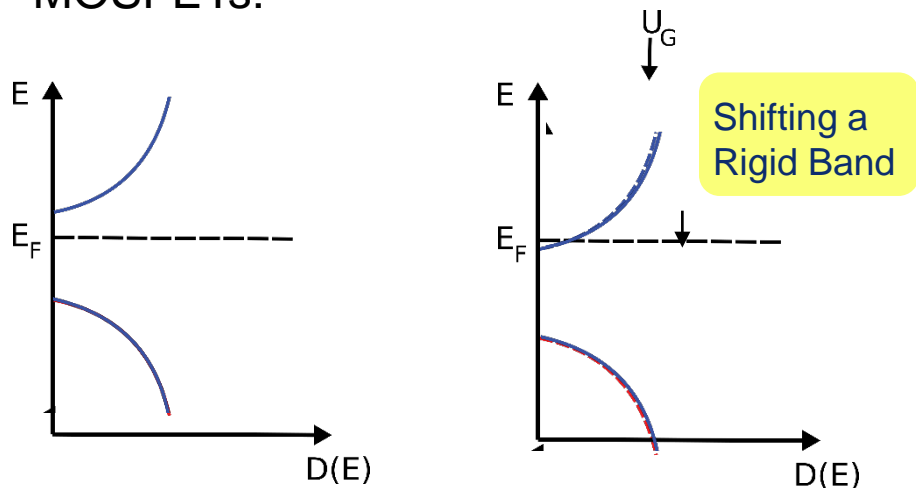
- Analog to Digital converters
- Neuromorphic Computing





# How to achieve low Subthreshold Swing? Transmission Engineering

MOSFETs:



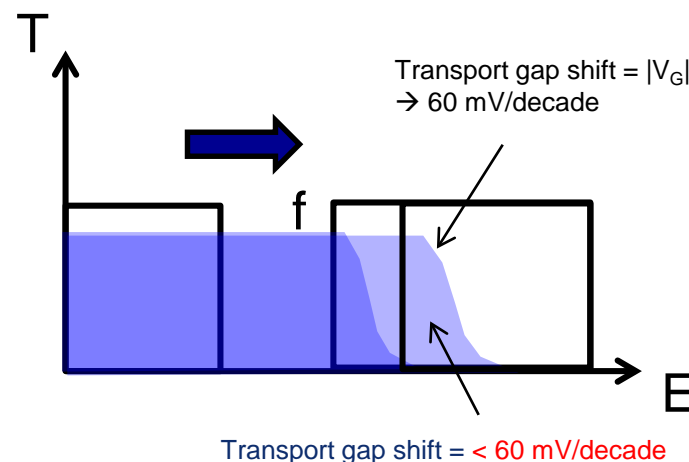
$$I = I_0 \int_{-\infty}^{+\infty} T (f_1 - f_2) dE$$

Landauer

$$S^{-1} = \underbrace{(q\alpha_G/k_B T)}_{\text{Electrostatic origin}} + \underbrace{d \ln T / dV_G}_{\text{Quantum Origin}} / \ln 10$$

Electrostatic origin  
(60 mV/dec)

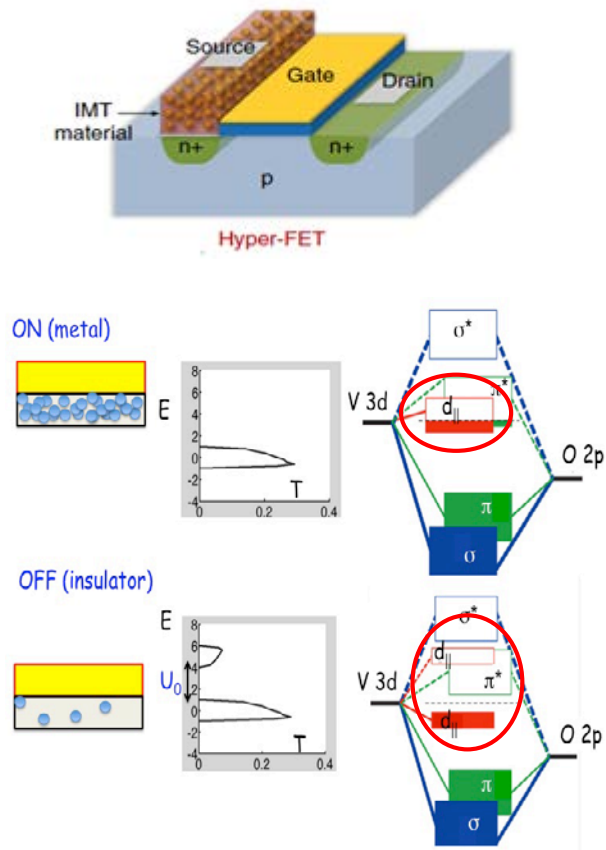
Quantum Origin





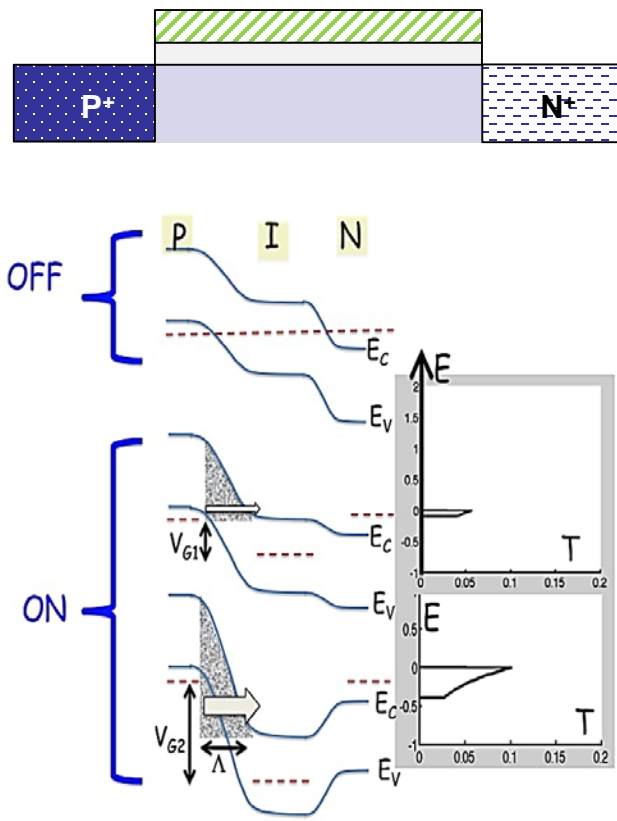
# Examples: Transmission Engineering

## MOTT FET



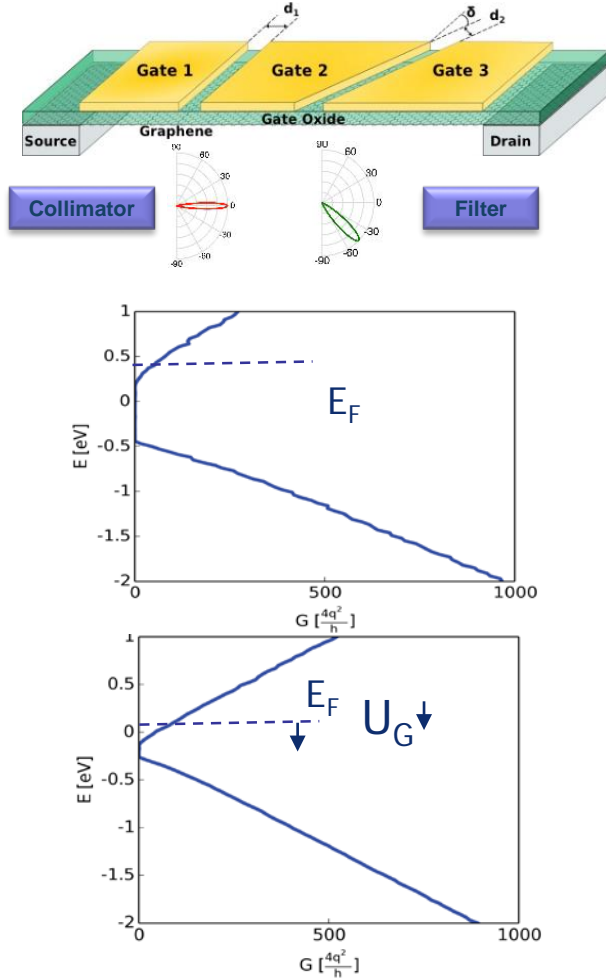
Band Modulation

## Tunnel FET



Channel Modulation

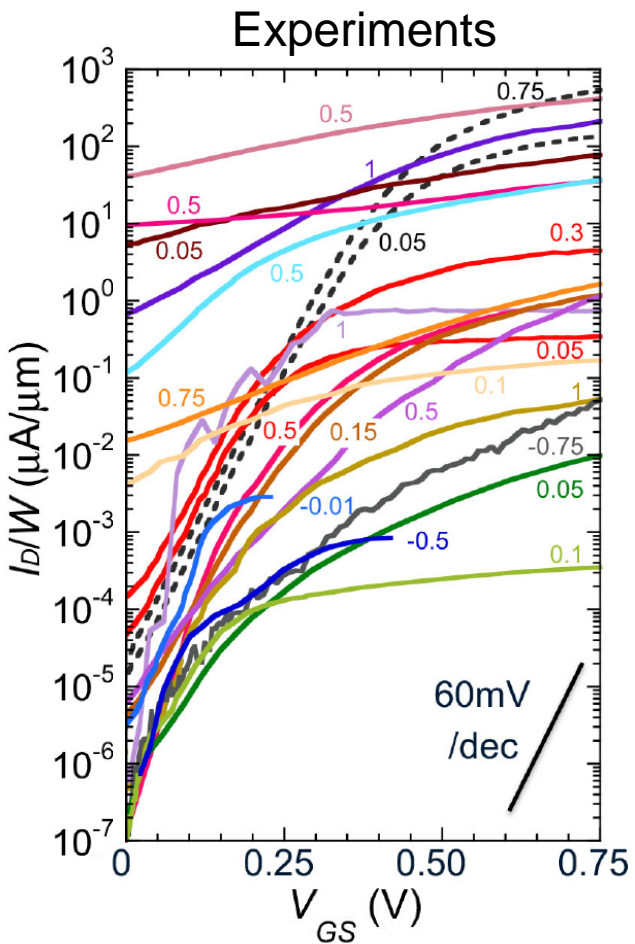
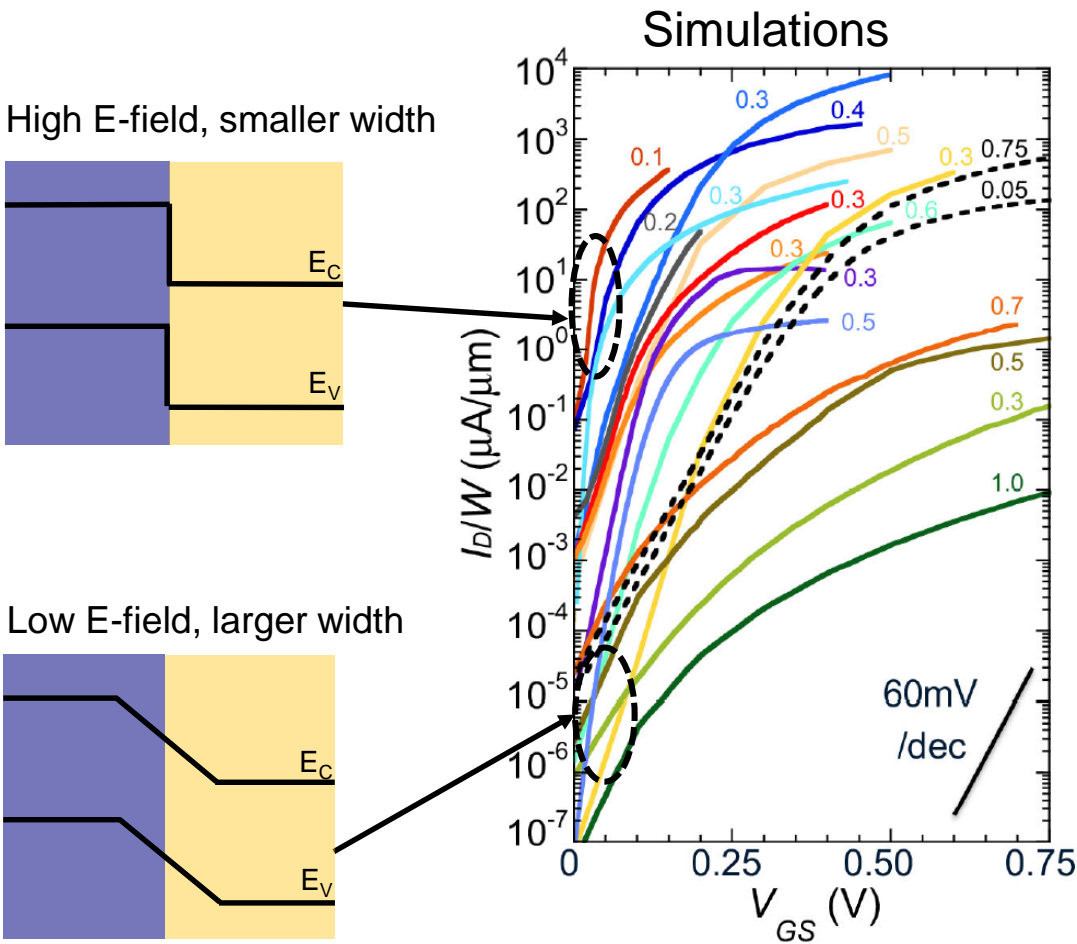
## Klein Tunnel FET



Transport Modulation

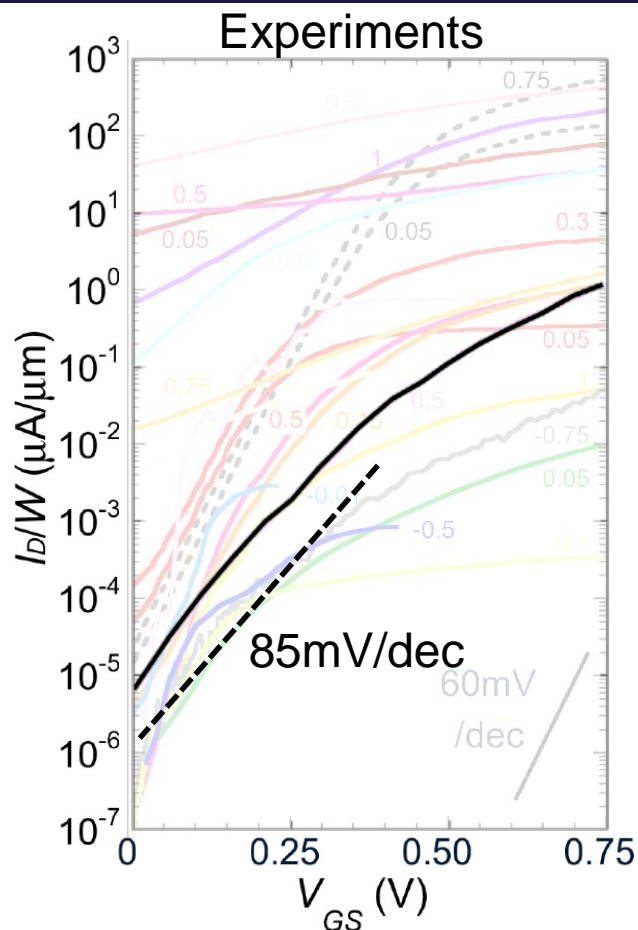
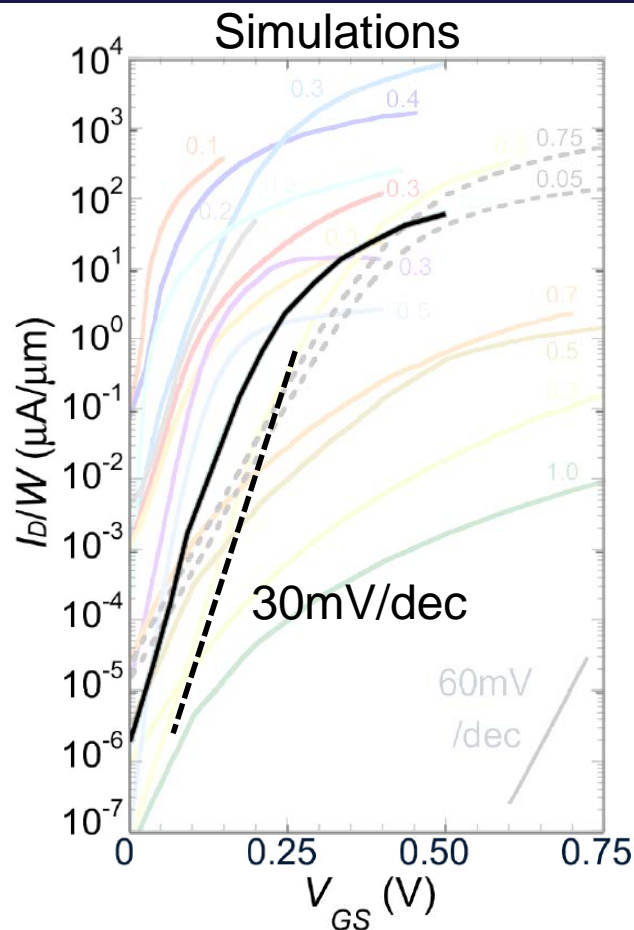


# Challenge of TFET





# Challenge of TFET

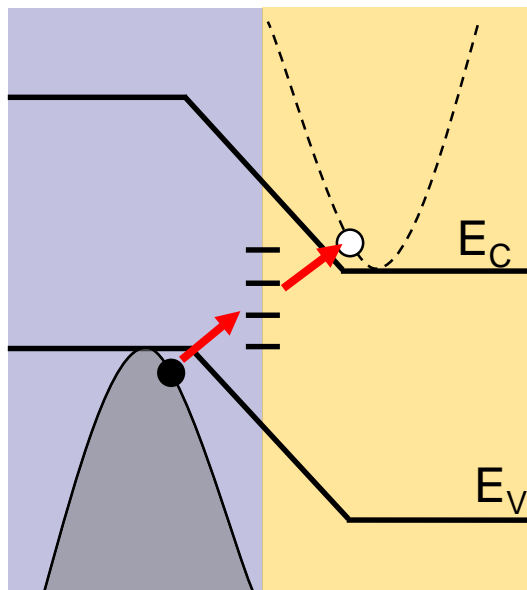


**TFET: simulations predict lower SS than experiments.**

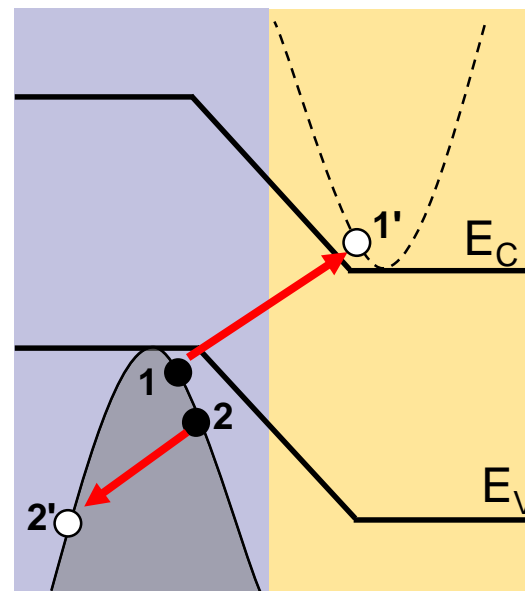
**What are the possible reasons?**



# What contribute to the off-current in reality?



**Trap Assisted Tunneling (TAT)**

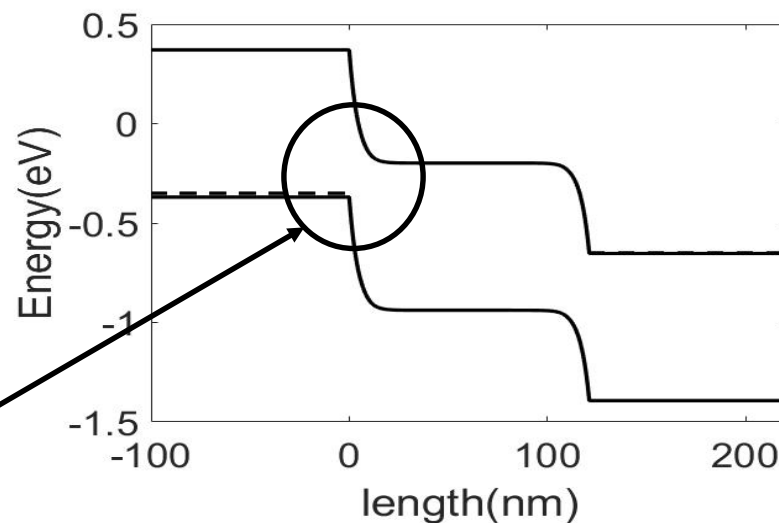
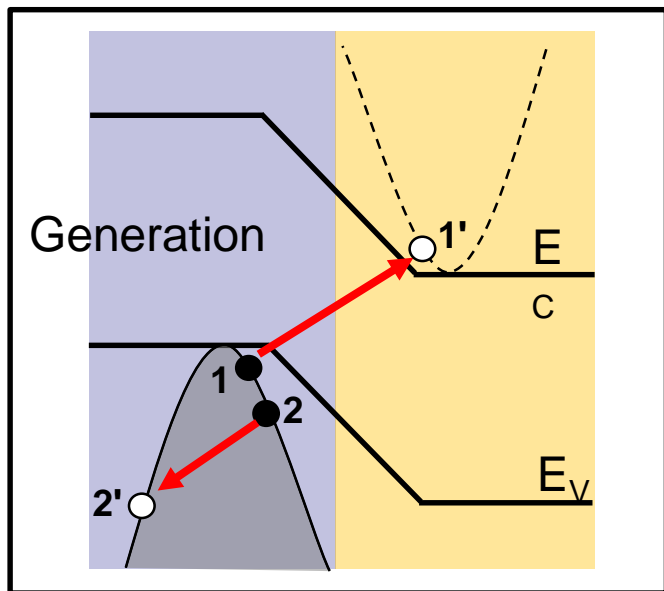
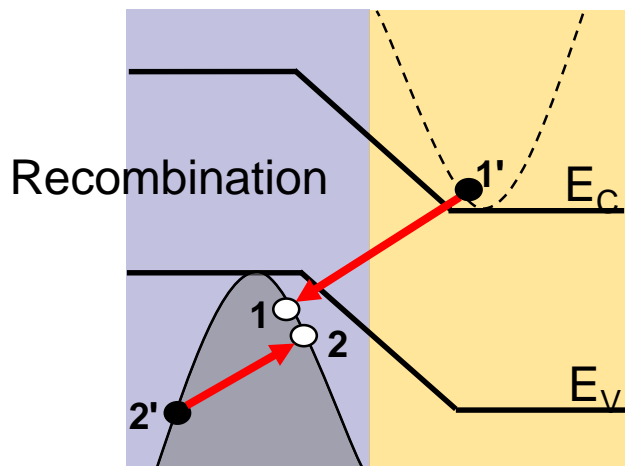


**e-e interactions like Auger**

**Auger effect introduces extra off-current even if traps/defects are eliminated**



# Why auger is important?



**Auger generation is important for low SS TFETs.**

$$U_{aug} \propto p(np - n_0p_0)$$





**Material parameters**



**Compact model of TFET**



**Auger effect in TFET**



# How to get correct material parameters?

## Modified tight binding

### What we need

$m^*$ , bandedge

Compact model  
of TFT

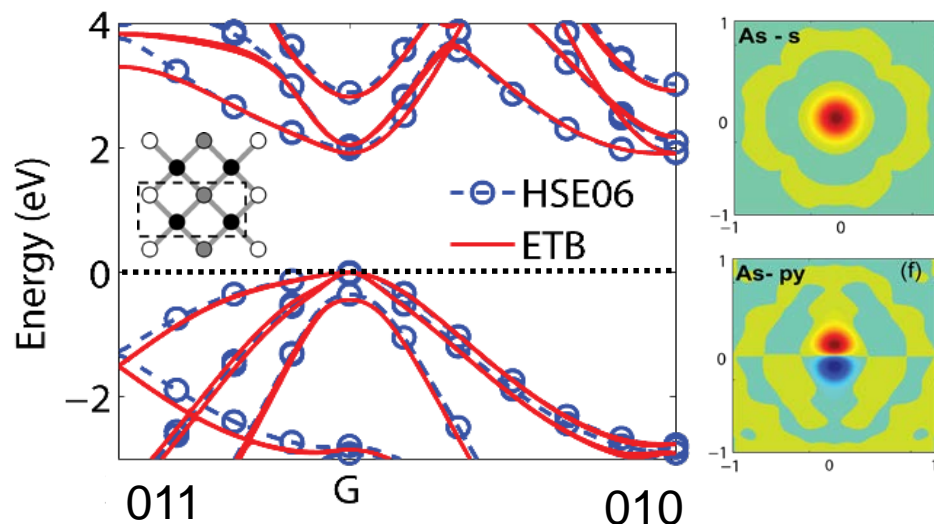
Wave function  
overlaps

Auger effect  
in TFET

ETB model:

- Calibrated with DFT band structures
- Calibrated with **DFT wave functions**
- **Match experiments**

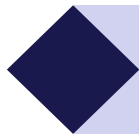
### ETB with explicit basis functions



AllInAs	Experiment	ETB
6ML	1.27 eV	1.24 eV
8ML	1.16 eV	1.17 eV

**Modified tight binding is used to extract material parameters**

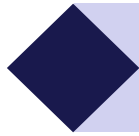
Alternate: Extended Huckel Theory (Ghosh)



**Material parameters**



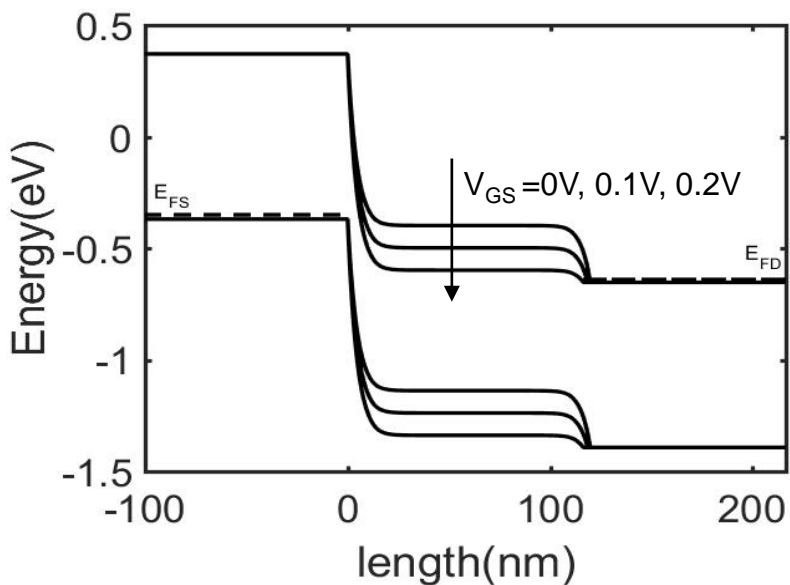
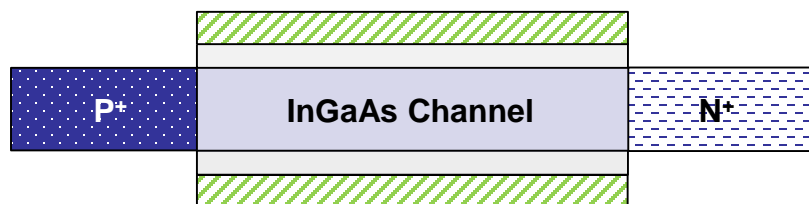
**Compact model of TFET**



**Auger effect in TFET**



# Chemistry Based Analytical Model: Using Simmons Equation



## ➤ Potential Model

- ❑ Solving Laplace Equation

## ➤ Two band model:

- ❑ Band-to-band tunneling

$$H(\mathbf{k}) = \begin{bmatrix} E_c(\mathbf{k}_{||}) & Ak_z \\ Ak_z & E_v(\mathbf{k}_{||}) \end{bmatrix} \frac{A^2}{E_c - E_v} = \frac{\hbar^2}{2m^*}$$

## ➤ Current:

- ❑ WKB+k-space integration

$$I = \int dE dk_{||} T_{WKB}(E, k_{||}) [f_S(E) - f_D(E)]$$

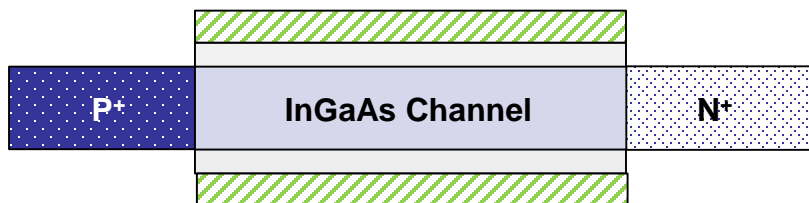
**Ballistic model for TFETs:  
Modified Simmons Equation using  
two band model**



# Calibration: Homojunction and Heterojunction

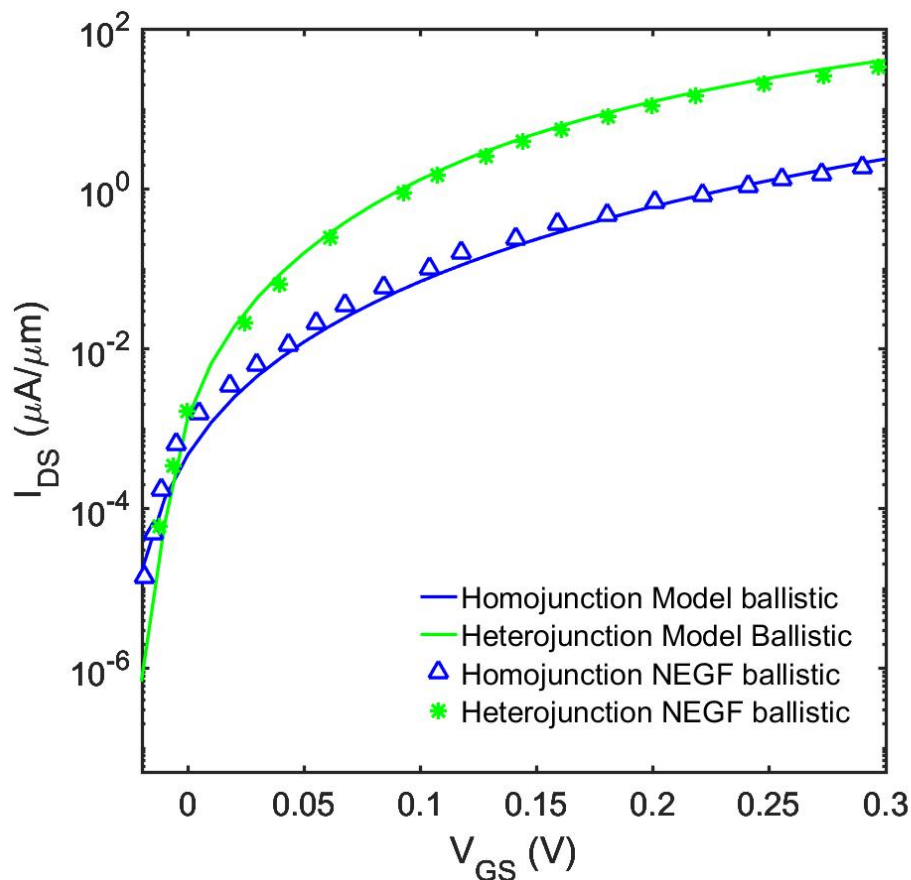
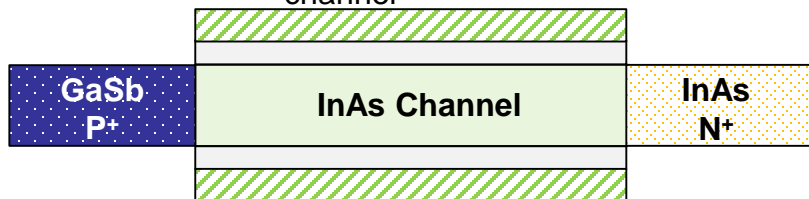
## Homojunction

$$L_{\text{channel}} = 100\text{nm}$$



## Type II Heterojunction

$$L_{\text{channel}} = 30\text{nm}$$

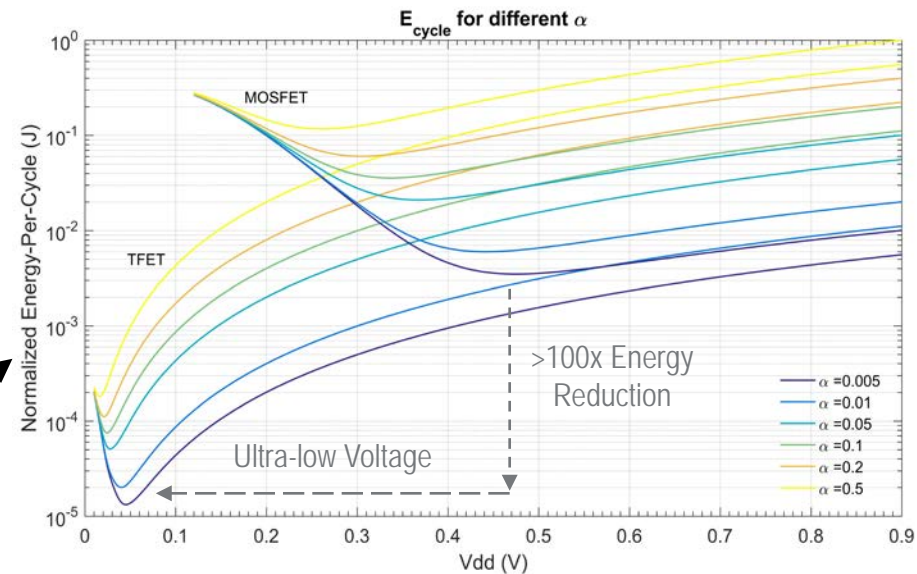
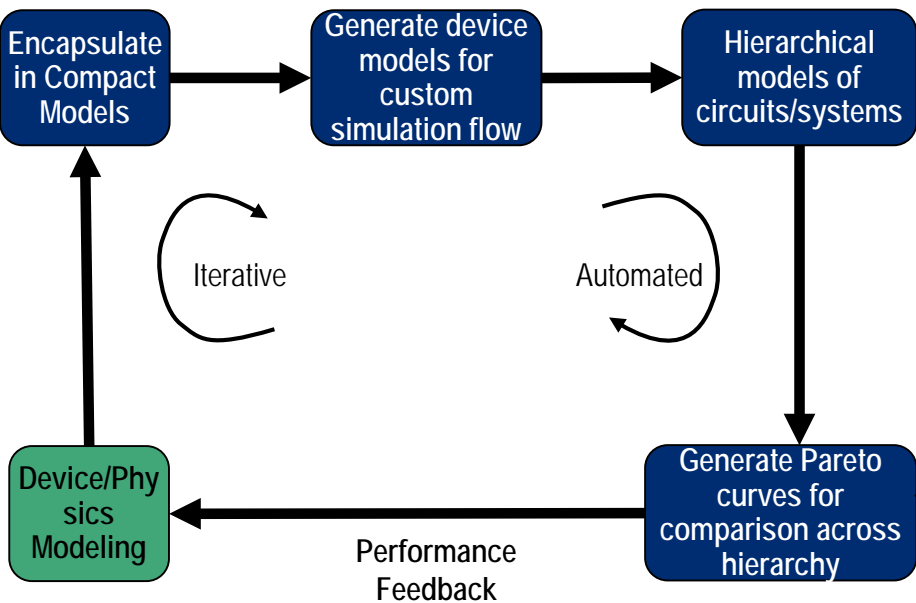


**Compact model match NEGF  
calculations (single Hetero TFET)**



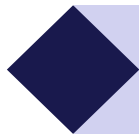
# Compact model based circuit simulation

## Rapid Circuit Simulation Flow for TFET Models



**Circuit design/analysis based on compact model**

**Collaborators: Daniel Truesdell, Ben Calhoun (UVA)**



**Material parameters**



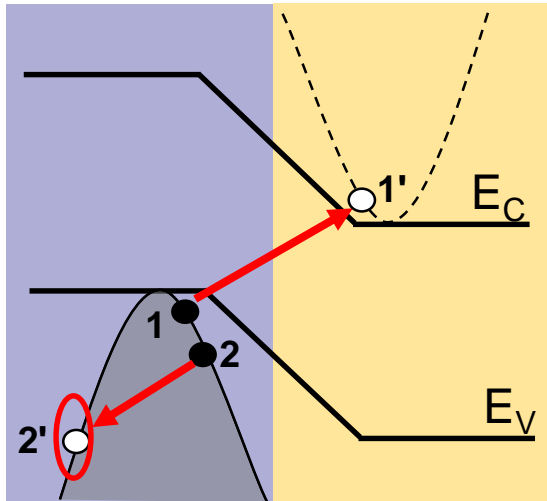
**Compact model of TFET**



**Auger effect in TFET**



# Physics of Auger process: basics



## Auger generation

- Dominates in the OFF state;
- Energy and momentum conserved;
- Depends on hole density  $p$  and wave function overlaps  $|\langle \psi_1 | \psi_{1'} \rangle|^2$

$$U \approx \frac{2\pi}{\hbar} \sum_{1,1',2,2'} P(1,1',2,2') |M|^2 \delta(E_1 - E_{1'} + E_2 - E_{2'})$$

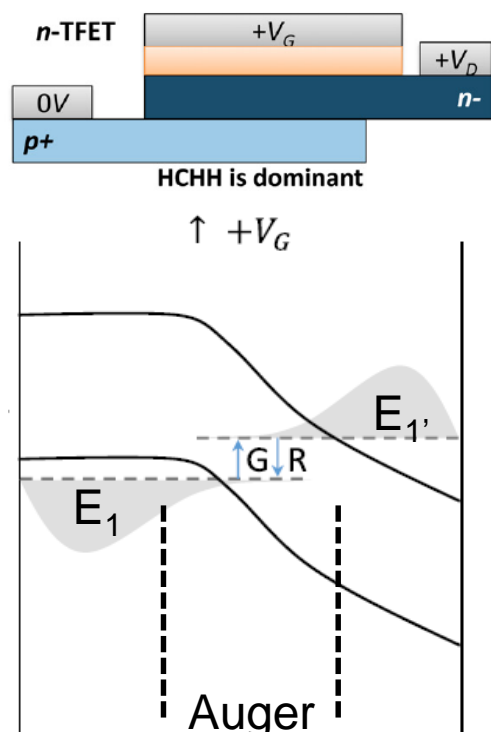
$$(1 - f_c(E_{1'})) D_c(E_{1'}) D_v(E_1) D_v(E_2) p(E_{2'}) |\langle \psi_1 | \psi_{1'} \rangle|^2$$

- Auger generation generate extra off current;
- Depends on the hole density and overlaps of CB and VB



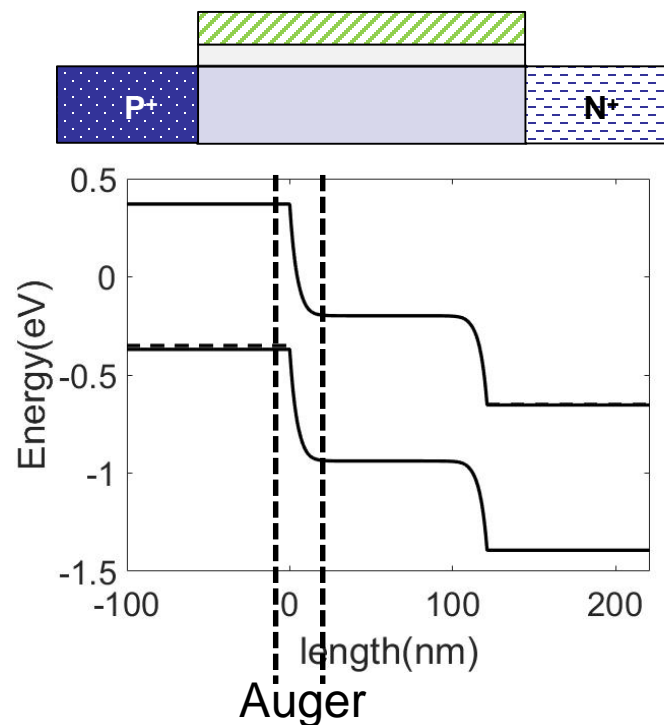


# Physics of Auger process: Auger in different device structures



## Auger in 2D:

- In a 2D plane
- **Discrete**  $E_1$  and  $E_1'$  in quantum wells



## Auger in Quasi 3D:

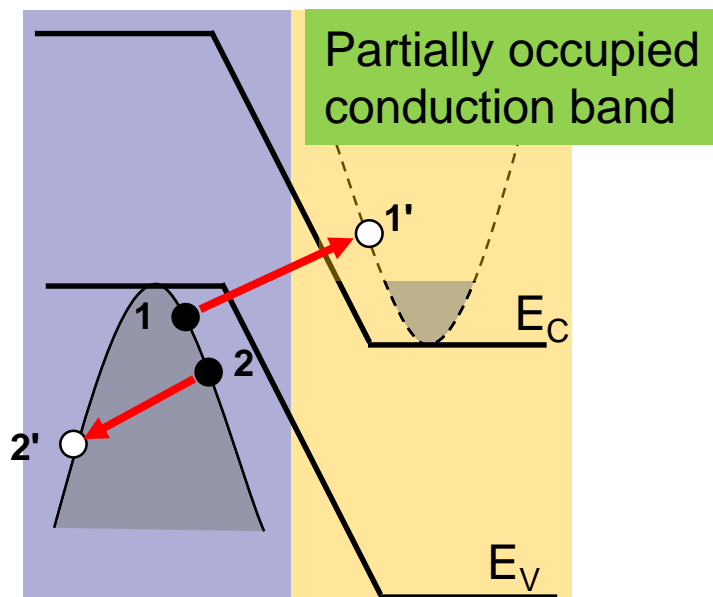
- In a 2D plane
- **Continuous**  $E_1$  and  $E_1'$

**Auger process in 2D and quasi 3D:  
Slightly different density of states**

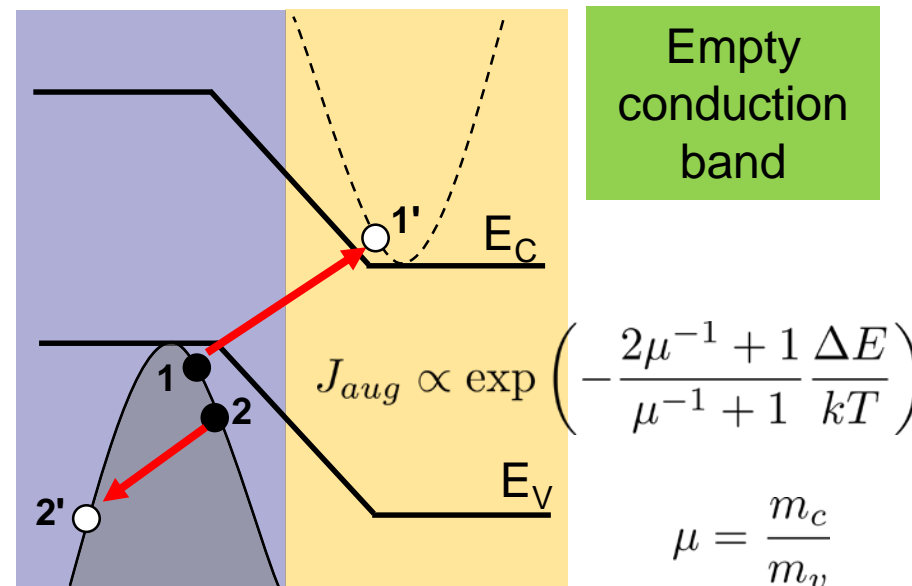


# Physics of Auger process: Auger process in ON-OFF states

Auger generation in the  
ON-state



Auger generation in the  
OFF-state

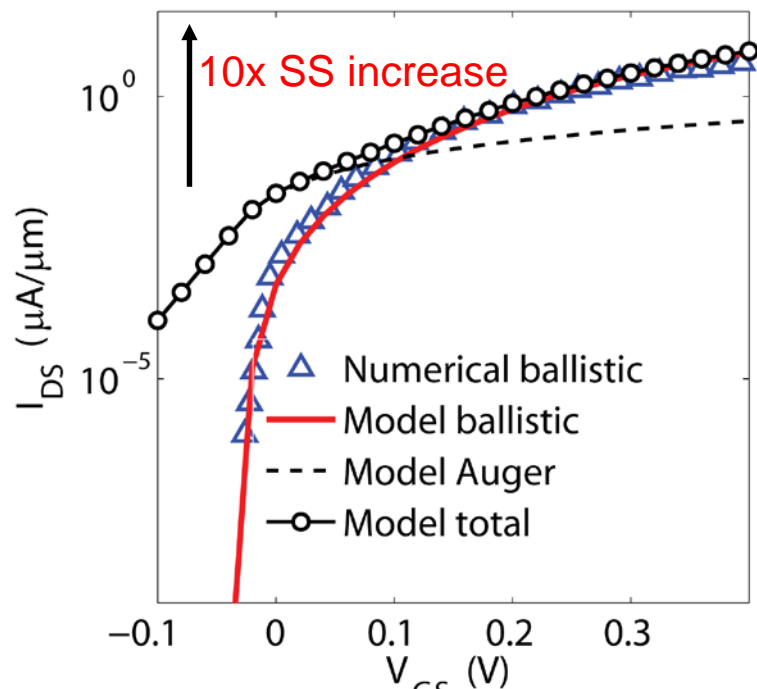


Limits the Subthreshold swing

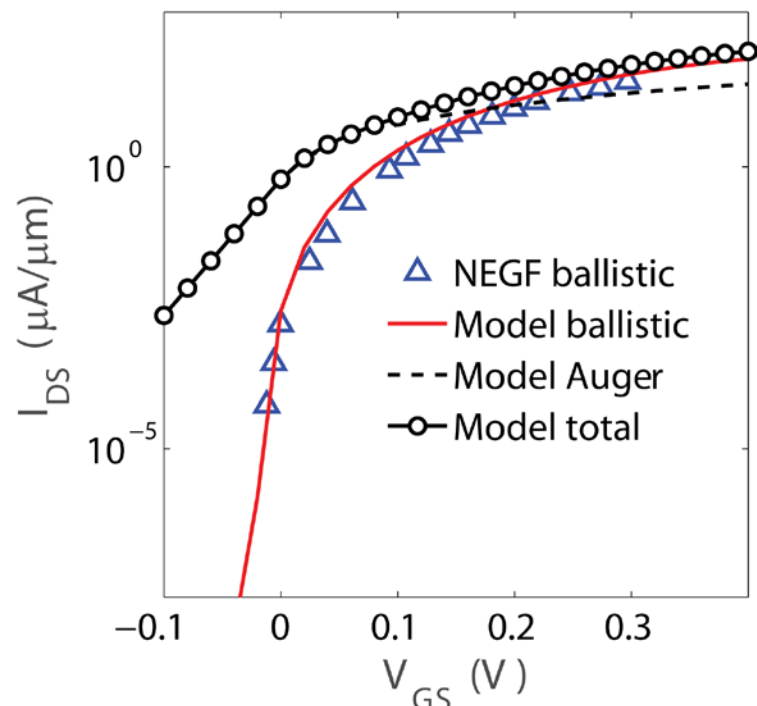
Occupancy of the conduction bands affect the  
Auger generation rates.



## Homojunction TFETs



## Single heterojunction TFETs



$$J_{aug} \propto \exp \left( -\frac{2\mu^{-1} + 1}{\mu^{-1} + 1} \frac{\Delta E}{kT} \right)$$

$$\mu = \frac{m_c}{m_v}$$



$$SS = \frac{\mu^{-1} + 1}{2\mu^{-1} + 1} \frac{kT}{q} \log 10 \approx \frac{\mu^{-1} + 1}{2\mu^{-1} + 1} 60 \text{mV/dec}$$

**TAT increases SS by a 2x  
( Sajjad, 2016)**

**Auger Effect limit the SS and off-current.**



## ➤ Compact model of TFET

- Compact model developed and benchmarked
- For both homojunction and heterojunction

## ➤ Auger effect in TFET

- Auger effect is calculated
- Auger effect limit the SS

$$SS \approx \frac{\mu^{-1} + 1}{2\mu^{-1} + 1} 60\text{mV/dec}$$

## ➤ TAT + Auger can explain discrepancy between simulation and experiment



Daniel Truesdell (University of Virginia)

Professor Benton Calhoun (University of Virginia)

Funded by: Energy-Efficient Computing: from Devices to  
Architectures(E2CDA)



Thank You